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		Application Number	10/672,110
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (Use as many sheets as necessary)		Filing Date	September 26, 2003
		First Named Inventor	Max Christian Schuermann, et al.
		Art Unit	2884
		Examiner Name	Otilia Gabor
		Attorney Docket Number	500814.20073
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NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
OG		"Reflectometer for EUV Lithography Components", Research Disclosure, July 2001, page 1146	
OG		V. Paret, et al. "Characaterization of Optics and Masks for EUV Litography," Microelectronic Engineering 61-62 (2002), Pages 145-155	
OG		H. Kondo, et al. "Development of EUV Reflectometer Using a Laser-Plasma X-Ray Source," Page 34	
OG		E.M. Gullikson et al. "A Soft X-ray/EUV Reflectometer Based on a Laser Produced Plasma Source" Journal of X-ray Science and Tecnology 3 (1192), Pages 283-299	
OG		D.L. Windt et al. "Multilayer Facilities Required for Extreme-Ultraviolet Lithography", 8257b Journal of Vacuum Science & Technology B (1994), Pages 3826-3832	
OG		M. Cui et al. "Synchrotron Radiation Soft X-ray Reflectometers and its Phusic Results" Nuclear Instruments and Methods in Physic Research A (1995), Pages 151-154	
OG		G. Schriever et al. "Laser-Produced Lithium Plasma as a Narrow-Band Extended Ultraviolet Radiation Source for Photoelectron Spectroscopy", Applied Optics (1998), Pages 1423-1248	

Examiner Signature	/Otilia Gabor/ (08/16/2006)	Date Considered	
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